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FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY, DOCKET NO. MICRON. 3DV2C1

APPLICATION NO. Unknown

†INFORMATION DISCLOSURE STATEMENT BY APPLICANT

APPLICANT SCHUEGRAF

(USE SEVERAL SHEETS IF NECESSARY)

FILING DATE GROUP
Herewith Unknown

U.S. PATENT DOCUMENTS								
EXAMINER INITIAL A			NAME CLASS		SUBCLASS	FILING DATE (IF APPROPRIATE)		
Sul	5,043,780	08/27/91	Fazan et al.					
aux.	5,102,832	04/07/92	Tuttle					
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12.1	5,320,880	06/14/94	Sandhu et al.					
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			FOREIGN PATENT DOCUMENTS				_
EXAMINER	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
INITIAL						YES	NO
as	403136361	06/11/91	Japan	257	306		
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EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)
41	Watanabe et al., "Hemispherical Grained Si Formation on in -situ Phosphorus Doped Amorphous-Si Electrode for 256Mb DRAM's Capacitor", IEEE Transactions on Electron Devices, Vol. 42, No. 7, pp. 1247-1253, July 1995
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